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(54) Title: METHOD OF MARKING MATERIAL AND SYSTEM THEREFORE, AND MATERIAL MARKED ACCORDING TO SAME METHOD

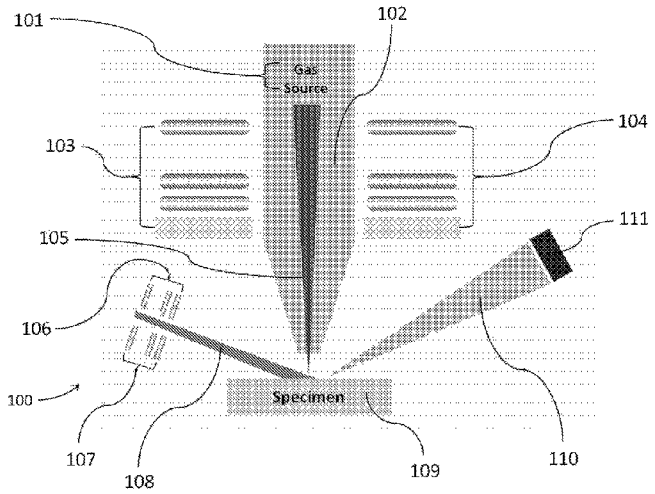


Figure 1

(57) Abstract: A method of forming one or more protrusions on an outer surface of a polished face of a solid state material,said method including the step of applying focused inert gas ion beam local irradiation towards an outer surface of a polished facet of a solid state material in a way of protruding top surface material;wherein irradiated focused inert gas ions from said focused inert gas ion bean penetrate the outer surface of said polished facet of said solid state material;and wherein irradiated focused inert gas ions cause expansive strain within the solid state crystal lattice of the solid state material below said outer surface at a pressure so as to induce expansion of solid state crystal lattice,and form a protrusion on the outer surface of the polished face of said solid state material.

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